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Notes:

1.0 Material

4.9% Mg doped Lithium Niobate, X=47% and Y=4.9%
 where A=number of moles of Li2O
 B=number of moles of Nb2O5
 C=number of moles of MgO in the melt, and
 $X=A/(A+B)*100\%$, $Y=3C/(A+5B+3C)*100\%$

2.0 Orientations

2.1 Wafer surface is normal to X axis $\pm 0.3^\circ$
 2.2 Flats
 2.2.1 Primary flat is normal to $\langle +Z \rangle \pm 0.3^\circ$.
 2.2.2 Secondary flat is $135^\circ \pm 1^\circ$ clockwise from the
 primary flat when viewing the $-X$ face.

3.0 Edge

3.1 All edges rounded with $R0.57 \pm 0.08$ mm.
 3.2 No chips greater than 0.5mm in penetration
 and 1.0mm in length.

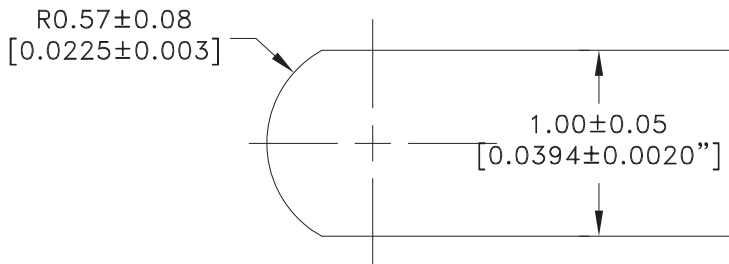
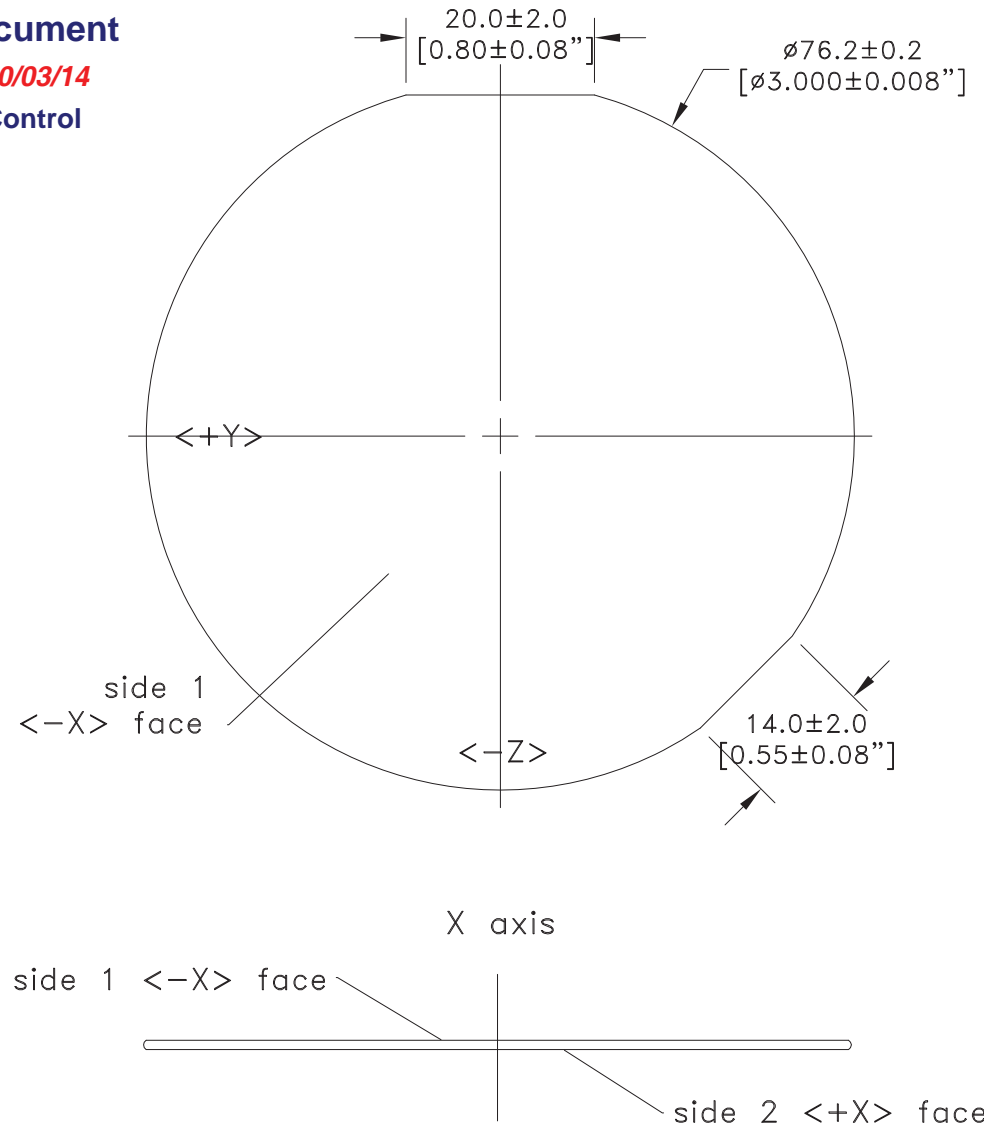
4.0 Surfaces

4.1 Side 1 $\langle -X \rangle$ face
 Polished 10-5 scratch-dig with 1mm edge exclusion.
 No pits or scratches visible with reflected light and
 unaided eye.
 4.2 Side 2 $\langle +X \rangle$ face
 Polished 60-30 scratch-dig with 1mm edge exclusion.
 Light pits and scratches visible with reflected light and
 unaided eye allowed.

5.0 Flatness

5.1 Warp $< 30\mu\text{m}$
 5.2 TTV $< 15\mu\text{m}$

Document
10/03/14
Control



Wafer Edge Detail, 20X

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Material: 4.9% Mg:LN	DR. TNG	09-23-14	
Unless otherwise specified, dimensions in mm	CHK.		
Tolerances		APPD.	Title: LNMG 4.9%, 76.2 ϕ x1.0mm, -X Po/Po, +Z FLT, TTV<15 μ m
Inches	Millimeters	Wafer Code: MNA--X:076.100DN	
X \pm 0.1 XX \pm 0.01 .XXX \pm 0.005 .XXXX \pm 0.0020	X \pm 0.5 .X \pm 0.25 .XX \pm 0.1 .XXX \pm 0.05	Customer Approval:	Size: A
Angles $\pm 0.5^\circ$		DO NOT SCALE DRAWING	Dwg. No: 97-02599-01
		Scale: 1.2:1	Rev: A
		Sheet 1 of 1	

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